



SURFACE PREPARATION SOLUTIONS

TECHNICAL ADVANTAGES

Ozone technology and proprietary processes such as Akrion Systems

Patented Pre-Epi Clean result in the best metal signature in the business.

Low metal contamination, coupled with high particle removal efficiency (> 97% @ 100nm) means better performance for your devices.

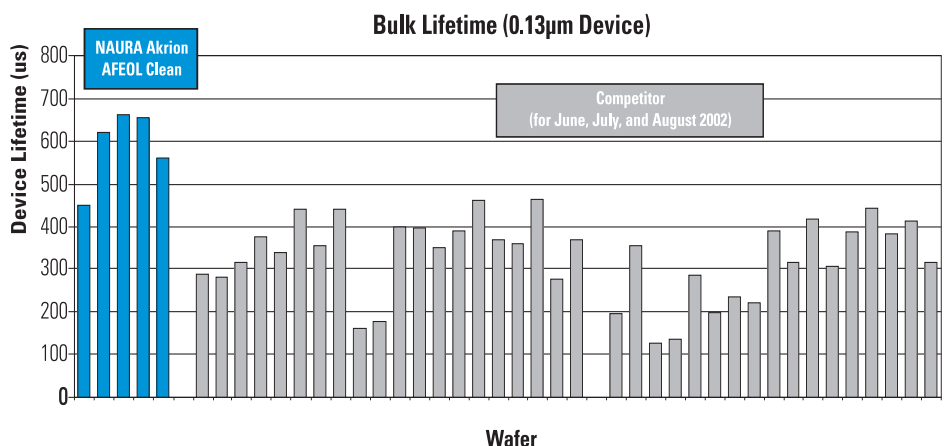
Advanced Front-end-of-line 200mm & 300mm Cleaning

AKRION SYSTEMS' FLEXIBLE PLATFORMS:

- Flexible solutions to fit your need
- Available in-situ tanks (GAMAplus) for smallest footprint
- Easily reconfigured for your changing process requirements
- Engineered for safety (S2, S8, CE, FM7-7)
- Proprietary ozone technology for metal contamination < 7E9 atoms/cm²
- Bi-directional processing capability for recipe flexibility
- SPC Host Interface/Trending
- Class 1 mini-environment (GAMA SERIES)
- Lowest Annual Consumable Parts Cost
- ICE-1™ concentration control maintains uniform chemical baths and extends bath life

METAL CONTAMINATION < 7 E9 ATOMS/CM² PER ELEMENT FOR BETTER PERFORMANCE

AFEOL Process: NAURA Akrion Beats the Competition



THE AKRION SYSTEMS DIFFERENCE:

- Worldwide process support
- 24 x 7 technical support
- Experienced service staff
- High Reliability: MTBF > 1500 hours
- Customer configurable flexible platforms

applications solutions

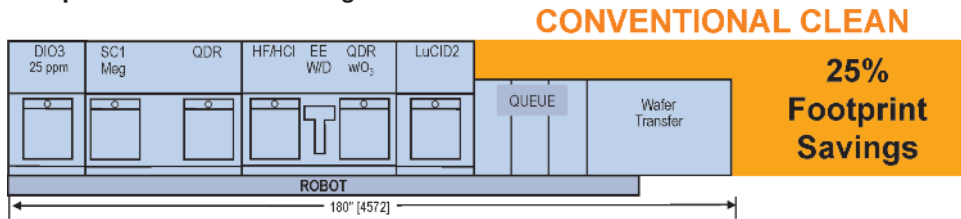
FLEXIBLE PRODUCT LINE FOR AFEOL:

The GAMA Series:

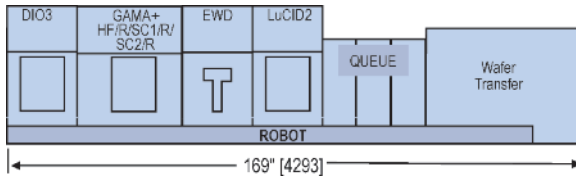
A modular, flexible and highly reliable tool set for FEOL cleaning.

- Single and dual modules for easy configuration
- GAMAplus in-situ modules reduce footprint and air interfaces

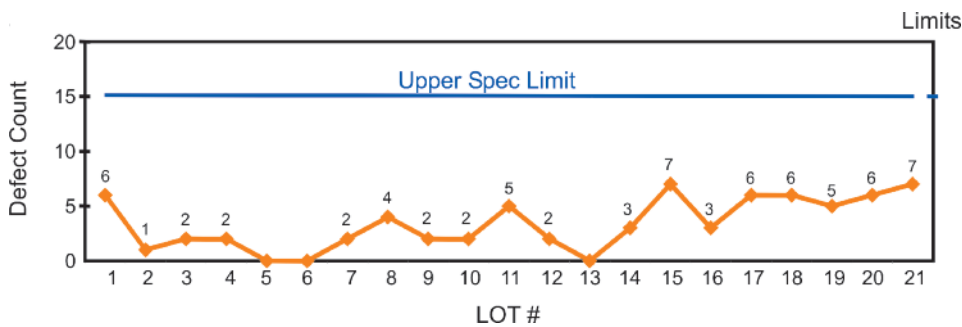
Sample 200mm GAMA Configuration



Sample GAMAplus Configuration Reduces Footprint



SUPERIOR PARTICLE PERFORMANCE:



Particle Adders @ 100nm

applications solutions developed for you

NAURA Akrion is the technology leader in process development, design and construction of advanced single-wafer and batch immersion surface preparation equipment to the semiconductor and other related industries.

With a primary focus on customer satisfaction, NAURA Akrion is committed to an organization-wide continuous improvement program - a program established to carry-out the improvement of key process steps and customer driven product enhancements. The company offers advanced automated solutions for cleaning a range of semiconductor-related devices, including ICs, MEMS, and photomasks.

NAURA Akrion offers reduced cost of ownership by providing small footprints, high uptime and throughput, efficient chemical management and environmentally benign technologies.